



Beam Initiative

The Fine Line: Spring 2016 Videos for the eBeam Community

Shot Talk - A Word from Our Sponsor

Aki Fujimura, CEO of D2S, recaps the buzz at the eBeam Initiative luncheon at the SPIE Advanced Lithography Conference along with a sneak peek at what's ahead for the Initiative later this year.



In a new addition to the Fine Line, Leo Pang, chief product officer of D2S, recaps the SPIE and eBeam Initiative highlights in [Chinese](#).



Video Archive

The Fine Line: Autumn 2015 Edition



Shot Talk:
Aki Fujimura of D2S



Tech Talk:
Markus Waiblinger,
ZEISS



Perspectives:
Industry luminary panel at
BACUS 2015 with RAVE, ZEISS
and D2S

Tech Talk

Dr. Hiroshi Matsumoto of NuFlare Technology introduces his company's new multi-beam mask writer, the MBM-1000, along with resolution performance results from an alpha version of the tool at the eBeam Initiative luncheon event at SPIE.



Perspectives

Doug Resnick of Canon Nanotechnologies—one of the eBeam Initiative's newest members—provides an insider's look at nanoimprint lithography (NIL) and how NIL is shaping up against other lithography approaches.



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The eBeam Initiative provides a forum for educational and promotional activities regarding new semiconductor manufacturing approaches based on electron beam (eBeam) technologies. Its goals are to reduce the barriers to adoption to enable more integrated circuit (IC) design starts and faster time-to-market while increasing the investment in eBeam technologies throughout the semiconductor ecosystem. For more information, please email requests@ebeam.org or visit www.ebeam.org